Equilibrium Chemical Vapor Deposition Growth of Bernal-Stacked Bilayer Graphene

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ABSTRACT.

Using ethanol as the carbon source, self-limiting growth of AB-stacked bilayer graphene (BLG) has been achieved on Cu *via* an equilibrium chemical vapor deposition (CVD) process. We found that during this alcohol catalytic (AC-) CVD, a source-gas pressure range exists to break the self-limitation of monolayer graphene on Cu, and at a certain equilibrium state it prefers to form uniform BLG with a high surface coverage of ~94% and AB-stacking ratio of nearly 100%. More importantly, once the BLG is completed, this growth shows a self-limiting manner and an extended ethanol flow time does not result in additional layers. We investigate the mechanism of this equilibrium BLG growth using the isotopically labeled ¹³C-ethanol and selective surface aryl functionalization, and results reveal that during the equilibrium ACCVD process, a continuous substitution of graphene flakes occurs to the as-formed graphene, and the BLG growth follows a layer-by-layer epitaxy mechanism. These phenomena are significantly in contrast to those observed for previously reported BLG growth using methane as precursor.

Graphene, a one-atom-thick crystal of *sp*²-bonsws carbon, has become one of the most attractive materials for next-generation technologies during the last decade due to its supreme mechanical, electrical, thermal and other properties.¹⁻³ To make the many different potential applications of graphene meet their requirements, various production methods for large-scale graphene have been developed, such as epitaxial growth on SiC,⁴ Ru⁵ and Pt,⁶ reduction of graphene oxide,⁷ liquid-phase exfoliation of graphite,⁸ and chemical vapor deposition (CVD) of hydrocarbons on transition metals.⁹⁻¹¹ As the most promising route to obtain graphene up to industrial scale, CVD-derived graphene using Cu substrates can exhibit transport properties equivalent to those of exfoliated graphene from mechanical exfoliation.^{12,13} It was discussed that during the CVD process, the growth of graphene is restricted to the Cu surface owing to the negligible solubility of carbon in Cu, and more importantly, the absence of Cu catalytic surface after one-layer carbon coverage makes it an ideal substrate for self-limiting growth of monolayer graphene (single-layer graphene, SLG).¹⁴

However, as a natural zero-bandgap semimetal, SLG has disadvantages to be fabricated into the core components of modern electronic devices such as field effect transistors, even though graphene has an extremely high electrical carrier mobility.¹⁵ Most of the bandgap opening trials for graphene are based on surface modifications *via* chemical processes,¹⁶ but they inevitably degrades the carrier mobility in graphene.¹⁵ AB- (Bernal-) stacked bilayer graphene (BLG) can develop a bandgap of up to 250 meV by applying a vertical electric field across the two layers,^{17,18} but facile, high-yield synthesis of AB-stacked BLG remains a significant challenge.¹⁹⁻ ²⁸ The key point for BLG growth by CVD was to overcome the self-limiting nature of SLG on Cu, in which it is critical to maintain or recover the Cu surface for the effective catalysis. Hence, compared with the simple self-limiting process of SLG on Cu surface, the growth of BLG has mainly been achieved by complicated pre-treatments or designed CVD process, such as spatially arranged Cu substrates,^{20,23} percentage-engineered Cu-Ni alloy as catalytic substrates,^{21,25} carefully adjusted nucleation pressure of methane,^{22,24} a high hydrogen ratio to expose the covered Cu surface,²³ or nonisothermal growth environment with variable temperatures.²⁸ It is generally believed that during the CVD process the second layer of BLG grows underneath the first-grown layer, as evidenced from isotope labeling experiments using methane,^{26,27} but a layer-by-layer epitaxy mechanism is proposed when spatially arranged Cu substrates are adopted, during which a van der Waals adhesion of the second layer onto the first-grown layer plays the most critical role.^{20,23} Besides using methane, graphene growth using ethane or propane as precursor can also exhibit BLG selectivity, but the growth mechanism of the second layer remains unknown.²⁹ We found these are not the case for the CVD process using ethanol, during which we can achieve a layer-by-layer epitaxial growth of equilibrium AB-stacked BLG.

In this work the self-limiting growth of AB-stacked bilayer graphene (BLG) has been demonstrated *via* equilibrium chemical vapor deposition (CVD). Using ethanol as the carbon precursor, it was achieved without involving any specially-designed CVD process, single-crystal or alloy-engineered metal substrates. We found that during this alcohol catalytic (AC-) CVD process, a source-gas pressure range exists to break the self-limitation of SLG on Cu, and at a certain equilibrium state it prefers to form uniform BLG with a high surface coverage of ~94% and AB-stacking ratio of nearly 100%. We explain its mechanism using the isotopically labeled ¹³C-ethanol and selective surface aryl functionalization, and results reveal that during ACCVD, a continuous substitution of graphene flakes occurs to the as-formed graphene, and the BLG growth follows a layer-by-layer epitaxy mechanism. These phenomena are significantly in contrast to those observed for previously reported BLG growth using methane as precursor.

RESULTS AND DISCUSSION

Ethanol has proven to be an efficient precursor for the SLG growth when low pressure (LP-) CVD and folded Cu foil enclosures are adopted.³⁰ The growth of SLG from ethanol follows a substrate-mediated mechanism, in which Cu surface morphology plays a significant role in the carbon diffusion process and the correlated graphene domain formation. A high degree of similarity exists between LPCVD-derived SLG using ethanol and methane as precursors, for example, the surface-mediated growth mechanism and the dendritic graphene domain shapes, and more importantly, the time-independence of SLG growth after the coverage of one-layer graphene over the Cu surface (the so-called SLG self-limiting process). This is attributed to the absence of a catalytic Cu surface to the stable precursor molecules when the growth of SLG is completed, so that no carbon clusters with dangling bonds for additional graphene layers can be provided.

However, the similarity in graphene growth between ethanol and methane is only valid when the precursor pressure is relatively low. As to methane, it maintains the self-limiting behavior of SLG within a wide range of flow rate or partial pressure. On the other hand, when the ethanol flow rate is increased, a pressure range exists to break the self-limitation of SLG, and additional layers will be formed. This provide the possibility to controllably synthesize graphene films with desired layer numbers. This hypothesis is supported by the experimental result that an ethanol partial pressure of 50 Pa and a growth time of 90 min can result in a high coverage of BLG and AB-stacking ratio. At this equilibrium state, ACCVD prefers to form uniform graphene with only two layers. Figure 1a shows a typical optical microscope (OM) image of a BLG film transferred onto a SiO₂/Si substrate. The thickness of the oxide layer on the substrate is 100 nm. In the OM image graphene and substrate both show as bluish color, but the sample uniformity



Figure 1. (a) Optical microscope (OM) image of a BLG film on a Si substrate with a 100nm-thick SiO₂ layer. (b) SEM image of as-grown ethanol-derived BLG film on a Cu foil. (c) Typical Raman spectra of BLG measured from four random spots in (a). (d) Transmittance spectra of a transferred BLG film (red), and a reference SLG film (blue). (e) SAED pattern of a bilayer graphene domain, which shows clear six-fold symmetry. (f) The spot intensities along the blue line in (e).

can be evaluated by the slight color contrast. No areas with different colors or contrast are apparent in this sample except for the substrate and sample edges, indicating that the layer number is uniform across the sample. The SEM image of as-grown graphene on Cu shown in Figure 1b also appears to be uniform with no layer contrast, consistent with the observation by optical microscopy. The visible white curves in the SEM image are natural wrinkles of the commercially-available Cu foils. The layer number of such ethanol-derived graphene is



Figure 2. Scanning Raman maps of ethanol-derived BLG for (a) I_{2D}/I_G , (b) FWHM of the 2D-band and (c) I_D/I_G . (d) The corresponding pie chart of graphene coverage for BLG, SLG and FLG in the ethanol-derived BLG film.

determined by Raman spectroscopy, and typical Raman spectra collected from circled areas (blue, green, black and red) in Figure 1a are shown in Figure 1c. All these spectra show Raman features of AB-stacked BLG, such as a 2D-band (~2700 cm⁻¹) to G-band (~1582 cm⁻¹) intensity ratio (I_{2D}/I_G) of approximately 1, and an asymmetric 2D-band with a full-width at half-maximum (FWHM) value of 45-60 cm⁻¹. The negligible D-bands at ~1340 cm⁻¹ in these spectra are indicative of the very high quality of these ethanol-derived BLG. Due to the optical absorption of exactly 2.3% for one graphene layer,³² the BLG nature of the graphene film can also be confirmed by UV–vis–NIR spectroscopy. After transferring to a quartz substrate, the graphene film exhibits a transmittance of 95.3% at 550 nm, very close to the theoretical value for BLG (95.4%). The transmittance of a SLG film is also shown in Figure 1d as a reference, which is ~97.4% at 550 nm. Selected-area electron diffraction (SAED) of these ethanol-derived BLG domains using TEM shows a single set of six-fold symmetric diffraction spots (Figure 1e), and

the corresponding spot intensities (Figure 1f) along the blue line in SAED pattern clearly indicate an AB stacking geometry for these graphene samples.

The uniformity and quality of ethanol-derived BLG were further determined by scanning Raman maps of the I_{2D}/I_G , FWHM of 2D-band, and the D-band to G-band intensity ratio (I_D/I_G), as shown in Figure 2a-c. In total 11 × 11 Raman spectra were collected over a 1000 μ m² area with ~3 μ m spacing resolution. We choose the range of Raman I_{2D}/I_G from 0.7 to 1.3 and the FWHM of the 2D-band from 45 to 60 cm⁻¹ to evaluate AB-stacked BLG features, as previously reported.³³ According to the combined results from Figure 2a and b, the ethanol-derived graphene film shows a remarkably high coverage of AB-stacked BLG of ~94%, SLG of ~2% and few-layer graphene (FLG) of ~4%, as shown in Figure 2d. It is noteworthy that twisted BLG with moiré pattern shows similar Raman features as SLG, but a much higher 2D/G ratio and a slight blueshift of the 2D-band.^{23,34} Careful investigations of the measured SLG Raman spectra shows no existence of such features from twisted BLG, indicating a 100% AB stacking for the BLG areas.

In order to have a better idea of how the equilibrium BLG grows on Cu surface using ethanol, we interrupted the CVD growth by cutting off the ethanol vapor after different growth periods, and present the results in terms of SEM images of as-grown graphene on Cu surface, as shown in Figure 3. When co-existing, BLG areas are displayed in darker color than SLG due to the different secondary electron yields. The brightest contrast is from Cu. After ethanol vapor was flowed for only 5 s, graphene islands were found to have rapidly nucleated and expanded to tens of micrometers, and obtained a coverage of over 80% of the Cu surface. The fast formation of graphene within such a short reaction time confirms the efficient conversion of ethanol



Figure 3. SEM images of as-grown graphene from ethanol on a Cu surface for different growth periods. The flow rate of ethanol was kept at 50 sccm and the partial pressure of ethanol is ~50 Pa. Two self-limiting processes for SLG and BLG are observed after 1 min and 90 min of graphene growth, respectively.

molecules into graphene. These islands are proven to be SLG, as characterized by Raman spectroscopy. Moreover, these SLG islands show dendritic patterns, suggesting a surfacemediated growth process.³⁰ After 20 s exposure to ethanol, most of the graphene islands have coalesced to form a large sheet, leaving only small unfilled gaps over the surface. Growth of a continuous film of graphene is obtained after 1 min ethanol flow and maintains the self-limiting behavior of SLG. Prolonged growth periods do not change this self-limiting behavior until after 30 min of ethanol flow, when new graphene islands start to nucleate. These new graphene islands, however, show apparent hexagonal shapes with rigid edges instead of dendritic shapes, indicating a different growth mechanism that is more related with the intrinsic structure of graphene itself. More and more new graphene islands appear with longer time of ethanol flow, and expand or coalesce to form the second layer of graphene. After 90 min the formation of a continuous second graphene layer completes, and more importantly, since then the BLG growth



Figure 4. SEM images of as-grown graphene on a Cu surface with an ethanol flow rate of 50 sccm at different growth temperatures. The corresponding pressure is ~50 Pa.

achieves an equilibrium state and starts the second self-limiting process but for BLG instead of SLG, as shown by the SEM images of as-grown BLG after 120 and 180 min growth.

The self-limiting growth of BLG shows a high sensitivity on the growth temperature and partial pressure/flow rate of ethanol, due to the significant roles they play in achieving the equilibrium state. The corresponding results are shown in Figure 4 and Figure 5, respectively. When the growth temperature is relatively low, such as 800 °C, after 90 min ethanol flow, the newly nucleated graphene islands cannot efficiently form a continuous second layer. Instead, these islands exhibit as small dots of less than 1 µm size and discretely decorate on the first layer background. An increased growth temperature to 850 °C significantly improved the formation of the second layer, in which most of the new graphene islands have coalesced into a continuous film after 90 min. The self-limiting growth of a complete second layer can be fulfilled with a temperature higher than 900 °C.

A proper partial pressure/flow rate of ethanol is also critical for the equilibrium CVD growth of BLG. As shown in Figure 5, when the partial pressure/flow rate is low, ethanol either forms SLG in a self-limiting manner (10 sccm),³⁰ or forms a non-uniform graphene film with clearly different layer numbers (30 sccm). On the other hand, when the partial pressure/flow rate is high,



Figure 5. SEM images of ethanol-derived graphene using various flow rates of 10, 30, 50 and 100 sccm, and growth periods of 60 and 90 min. The partial pressures of ethanol for these flow rates are approximately 10, 30, 50 and 100 Pa, respectively. These recipes show no successful growth of BLG, suggesting the existence of a pressure/flow rate equilibrium to realize the BLG growth.

islands of three or more layer easily nucleate when the growth time is less than 60 min, and expand to form graphene with different layers after 90 min. These temperature and flow rate dependences suggest the current BLG growth parameters are significant to the equilibrium BLG growth process, not only to initialize the growth of the second layer but also to make it complete and self-limiting.

To further investigate the mechanism for this equilibrium growth of self-limiting BLG using ethanol, we adopted an isotope labeling method to track the graphene growth route during the CVD process. Due to the expense of ¹³C₂H₅OH, its continuous flow for 90 min is not economically sustainable. Our alternative strategy is to grow a uniform SLG by ¹³C₂H₅OH by no-flow ACCVD and demonstrate its equivalence with flow ACCVD, and then use ¹²C₂H₅OH to continue the growth for the following 90 min. As shown in Figure S1, no-flow ACCVD is efficient to form SLG with high quality, and its dendritic island pattern demonstrates the same surface-mediated process as when flow ACCVD is employed. For BLG growth using isotopic ethanol sources, CVD trials using 3 min ¹³C₂H₅OH followed by 0, 10, 30 and 70 min ¹²C₂H₅OH were performed. Because the total growth time is less than 90 min, these samples are not fully covered by BLG areas, and the co-existence of SLG and BLG may help clarify the BLG growth mechanism using ethanol.

We first characterized the areas that are only covered by SLG in these samples, and their corresponding OM images and scanning Raman maps of the G-bands for ¹²C and ¹³C are shown in Figure 6. Only isotopically pure ¹²C- or/and ¹³C-SLG was observed in these samples, evidenced by the Raman G-band peaks located at ~1582 cm⁻¹ and ~1525 cm⁻¹, respectively. After the formation of SLG by ¹³C₂H₅OH no-flow ACCVD for 3 min, the followed 10 min ¹²C₂H₅OH flow did not change the isotope composition in formed SLG, as shown by the Raman maps of G-band peaks. However, when the ¹²C₂H₅OH flow time was increased to 30 min, some of the ¹³C areas in formed SLG were substituted by ¹²C areas, and these ¹³C-SLG and ¹²C-SLG areas showed a clear complementary pattern. This pattern is different from the ring-like pattern when sequentially introduced methane is used, in which no such substitution effect has been observed.²⁶ It needs to be noticed that no G-band peak located at the middle



Figure 6. OM images and scanning Raman maps of ¹²C and ¹³C G-band peaks for the SLG areas in ethanol-derived graphene samples grown by: (a) 3 min ¹³C₂H₅OH; (b) 3 min ¹³C₂H₅OH followed by 10 min ¹²C₂H₅OH; (c) 3 min ¹³C₂H₅OH followed by 30 min ¹²C₂H₅OH; and (d) 3 min ¹³C₂H₅OH followed by 70 min ¹²C₂H₅OH. All ¹³C₂H₅OH trials were conducted by no-flow CVD with 0.4 μ L ¹³C₂H₅OH, whereas all ¹²C₂H₅OH trials were flakes are observed in (c) and (d).

position (~1553 cm⁻¹) were observed in this sample, proving that the ¹²C and ¹³C atoms were not well mixed and the substitution of ¹³C by ¹²C occurred only in a flake-by-flake manner. When the ¹²C₂H₅OH flow time was further increased to 70 min, the isotope substitution became more severe and more than half of the ¹³C areas in initially formed SLG were substituted by ¹²C areas, with the clear flake-by-flake manner.



Figure 7. Raman analysis of a graphene sample with co-existences of both SLG and BLG and both ¹²C and ¹³C areas. (a) OM image of the measured sample, in which SLG and BLG areas are clearly visible by their different color contrast. (b) Graphene flakes with different layer numbers and isotope compositions. (c, d) Scanning Raman maps of ¹²C and ¹³C G-band peaks in the sample, respectively. (e) Typical Raman spectra measured from circled spots in (a), and the decomposed 2D-band peaks for ¹²C BLG and ¹²C&¹³C BLG.

What is of more importance is the formation of AB-stacked BLG. Figure 7 shows the Raman analysis of a graphene sample with co-existing SLG and BLG, as well as both ¹²C and ¹³C areas. This was grown from 3min ¹³C₂H₅OH no-flow ACCVD followed by 70 min ¹²C₂H₅OH flow ACCVD. The OM image of measured area on this sample is shown in Figure 7a, in which the

SLG and BLG areas are clearly visible by their different color contrast. Scanning Raman results show that the SLG and BLG areas are formed by only ¹²C atoms or both ¹²C and ¹³C atoms, but not by only ¹³C atoms. Graphene flakes with different layer numbers or isotope compositions are indicated by different colors in Figure 7b, and the SLG and BLG areas are circled by pink and blue lines, respectively. Most (~93%) of the SLG area is composed of both ¹²C and ¹³C atoms, due to the isotope substitution from sequentially introduced ${}^{12}C_2H_5OH$, as previously mentioned. On the other hand, for BLG area in this sample, only ~35% is composed of both isotopes, whereas the rest is formed by only ¹²C atoms. The G-band Raman maps of ¹³C and ¹²C graphene flakes are shown in Figure 7c and d, respectively, but these G-band patterns for ¹³C and ¹²C graphene are not consistent with the SLG and BLG distributions. This inconsistence shows that the isotope substitution has no dependence on the graphene layer numbers. Typical Raman spectra of ¹²C SLG, ¹²C&¹³C SLG, ¹²C BLG and ¹²C&¹³C BLG are shown in the left panel of Figure 7e, measured from the circled areas by brown, cyan, violet and orange in Figure 7a, respectively. For ¹²C&¹³C SLG, its Raman spectrum consists of both ¹²C and ¹³C G-band peaks, and both the I_{2D}/I_G for ¹²C and ¹³C peaks are larger than 3. We characterized this Raman spectrum as from ¹²C&¹³C SLG other than from a twist ¹²C&¹³C BLG is due to the fact that no frequency shift is observed for the two 2D-band peaks, as well as the slightly brighter color for SLG in the OM image. The right panels of Figure 7e show the decomposed Raman spectra for ¹²C BLG and AB-stacked ¹²C&¹³C BLG. The spectra of ¹²C BLG and ¹²C&¹³C BLG are fitted by four and eight symmetric Lorentzian shapes, respectively, representing their four and eight allowed transitions. The decomposition of the 2D-band Raman peak in ¹²C&¹³C BLG into eight peaks also demonstrates a modified electronic dispersion, but is still consistent with the doubleresonance Raman theory for 2D-band in AB-stacked BLG.



Figure 8. (a) Schematic of aryl-group functionalization to BLG, which only modifies the top layer of a BLG film. (b) Typical Raman spectra of a modified isotopically labeled graphene sample, measured from ¹²C&¹³C SLG, ¹²C BLG and ¹²C&¹³C BLG areas. (c) Enlarged D-band spectra in the highlighted areas in (b). Red and grey arrows indicate the newly generated defect peaks in graphene and peaks from aryl groups, respectively.

A most important issue in the growth mechanism study of equilibrium BLG is the growth sequence of the two layers. It is generally believed that when methane is used as precursor, the second graphene layer is grown underneath the first one,^{26,27} at the same nucleation spots but slower growth rates. However, some reports also proposed that the second graphene layer can form above the first one, as long as carbon fragments catalyzed from elsewhere are brought above the first layer and adhere by van der Waals interaction.^{20,23} To characterize the growth sequence of the two layers in ethanol-derived BLG, we employed aryl-group functionalization on isotopically labeled BLG samples to create sp^3 -type defects on the top surface of graphene, using 4-nitrophenyl diazonium tetrafluoroborate (NO₂-C₆H₄N₂+BF₄⁻),³⁵ and detect the corresponding changes in the Raman spectra from different modified SLG and BLG areas. When BLG is transferred onto a Si/SiO₂ substrate, the NO₂-C₆H₄N₂+BF₄⁻ molecules selectively modify

the top layer and leave the bottom layer unchanged. A schematic of aryl-group functionalization for BLG is shown in Figure 8a, and the Raman spectra of different modified areas are shown in Figure 8b. The D-band peaks highlighted by yellow in Figure 8b are enlarged in Figure 8c, and red and grav arrows indicate the newly generated defect peaks in graphene and peaks from arvl groups, respectively.³⁶ After aryl-group functionalization, for ¹²C&¹³C SLG, two apparent Dband peaks (indicated by red arrows) were detected at ~1290 and 1340 cm⁻¹, corresponding to the defect peaks in ¹³C and ¹²C graphene, respectively. The assignment of the 1290 cm⁻¹ peak to the D-band peak of ¹³C graphene is based on the aryl-group functionalization results of isotopically pure ¹³C graphene. The co-existence of these two D-band peaks shows that both ¹²C and ¹³C graphene flakes are modified, which also confirms the one-layer nature of this graphene area. However, for modified ¹²C&¹³C BLG, only one D-band peak located at ~1340 cm⁻¹ was observed, which was from the defect sites in ¹²C graphene flakes. Because the second layer in the isotopically labeled BLG is formed entirely from ¹²C₂H₅OH, considering that aryl groups only modify the top layers, these surface functionalization experiments clearly demonstrate that the new graphene layer is grown on top of the previous one when ethanol is used as the precursor. This result is consistent with the previously shown SEM images with newly grown second layers, which have graphene-related hexagon shapes instead of Cu-related dendritic shapes.

Based on the evidences shown above, we propose the mechanism of equilibrium BLG growth from ethanol as a layer-by-layer epitaxy. As shown in Figure 9, with a proper partial pressure of ethanol, after the formation of SLG from a surface-mediated process, the graphene growth first maintains the self-limiting manner for a certain period, but with flake substitution triggered by newly introduced ethanol. We attribute the origin of this substitution to the etching effect of some decomposed products from ethanol, such as H₂, H₂O, *etc.* With longer growth time and a



Figure 9. (a) Schematic the layer-by-layer epitaxy mechanism for equilibrium BLG growth using ethanol as CVD precursor.

proper kinetic equilibrium, carbon fragments formed by decomposed ethanol products start to nucleate on top of the first graphene layer by the van de Waals interaction, then expand and coalesce into a continuous layer with a slower growth rate than the first layer. Moreover, during the growth of the second graphene layer, flake substitution occurs in both layers.

CONCLUSIONS

We demonstrate the first self-limiting growth of AB-stacked BLG films on Cu using an equilibrium ACCVD process, without any other specially designed growth process, single-crystal or alloy-engineered metal substrates. During the graphene growth at the equilibrium state, two self-limitations occur at different growth stages for SLG and BLG, respectively. SLG is formed first with a surface-mediated mechanism, followed by its self-limiting period for ~30 min. Hexagonal shaped graphene grains of the second layer appear later and expand into a continuous sheet with a slower rate, and the growth of this BLG film maintains the self-limiting manner for no shorter than 90 min. The equilibrium BLG has a high surface coverage of ~94% and AB-stacking ratio of ~100%. Isotope-labeling experiments using ${}^{12}C_{2}H_{5}OH$ and ${}^{13}C_{2}H_{5}OH$ and

selective surface aryl functionalization on the top layer of grown ¹²C&¹³C BLG prove that this self-limiting growth of BLG using ethanol occurs with a layer-by-layer epitaxy mechanism with continuous flake substitution in formed layers. This is different from the growth mechanism of BLG using methane as carbon precursor, in which no substitution occurs and the new layer grows underneath the formed layer. Although only the equilibrium growth of self-limiting AB-stacked BLG is presented here, we believe that such growth can be extended to uniform graphene with more layers, hence help understand more thermal dynamic processes for graphene growth and advance the ongoing efforts toward controlled and inexpensive approaches for scalable graphene production.

METHODS

Graphene synthesis. An ACCVD process was used for the self-limiting BLG growth, as described elsewhere.³⁰ In brief, after surface cleaning the commercially available Cu foil (10- μ m-thick, Nippon Denkai Co., Ltd.) was folded into an enclosure with the remaining three sides carefully crimped, and loaded into a hot-wall CVD quartz chamber (26 mm, i.d.). The enclosure was annealed at 1000 °C for 20 min before 50 sccm ethanol vapor was introduced. The partial pressure of ethanol was kept at approximately 50 Pa. The growth lasted for different periods of several seconds to 180 minutes. For BLG growth from isotopic ethanol sources, an equivalent no-flow CVD process was adopted.³¹ In this case, 0.4 μ L ¹³C₂H₅OH (99%, Cambridge Isotope Laboratories, Inc) was first introduced for 3 min to finish the growth of the first layer, followed by evacuating the ¹³C residues and introducing 50 sccm ¹²C₂H₅OH for the desired growth time.

Graphene transfer. For graphene transfer, the inside surface of unfolded Cu foil enclosure was spin-coated with a thin layer of poly(methyl methacrylate) (PMMA) and baked at 150 °C,

and the outside surface was treated by O₂ plasma to remove the unnecessary graphene and graphite layers. The supported Cu foil was then etched by 1 M FeCl₃ solution to isolate the graphene/PMMA film for its transfer to arbitrary substrates. Finally, the PMMA layer was removed by a hot acetone bath. If the BLG was transferred to SiO₂/Si substrate for surface functionalization, it needs an additional annealing process at 360 °C for 3 hours with a 100 sccm hydrogen flow to increase the interface adhesion between graphene and the substrate.

Surface functionalization. The selective surface functionalization of BLG top layer was conducted using a mixed aqueous solution of 30 mL 20 mM 4-nitrobenzenediazonium tetrafluoroborate and 6 mL 1% w/v sodium dodecyl sulfate. Annealed BLG/SiO₂/Si sample was immersed in the solution and gently stirred for 5 hours at 35 °C, and then placed in DI water overnight to remove the salt residues. Finally the sample was repeatedly rinsed by DI water and dried by nitrogen flow.

Characterization. Characterization of as-grown and transferred graphene samples was carried out by scanning electron microscopy (SEM, 5 kV, S-4800, Hitachi Co., Ltd.), transmission electron microscopy (TEM, 80 kV, JEM-2100, JEOL Co., Ltd.), UV-vis-NIR spectroscopy (UV-3600, Shimadzu Co., Ltd.), and micro-Raman spectroscopy (Renishaw inVia system, Renishaw plc).

Supporting Information. Supporting figures. This material is available free of charge *via* the Internet at http://pubs.acs.org.

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TOC figure

Equilibrium Chemical Vapor Deposition Growth of Bernal-Stacked Bilayer Graphene

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Figure S1. Comparisons of ${}^{12}C_2H_5OH$ (50 sccm) flow CVD and its equivalent ${}^{13}C_2H_5OH$ (0.4 µL) no-flow CVD experiments.



Figure S2. (Left) Typical Raman spectra of an isotopically pure ¹³C graphene sample before (red) and after (blue) the aryl-group functionalization. (Right) Enlarged spectrum within 1250 to 1500 cm⁻¹ of the ¹³C graphene after aryl-group functionalization. Red and grey decomposed peaks indicate the newly generated defect peak in graphene and peaks from aryl groups, respectively.